A Facile Protocol for Designing the CdS/PbS Multi Layered Quantum Dots with Enhanced Photoelectrochemical Performance

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Photocatalysts play a vital role in solar cell performances; solar cells are an effective source of green energy. In this paper, a facile and affordable protocol for designing an effective photoanode based on the quantum dot was introduced. The multi-layered quantum dots containing CdS and different layers of n-type of PbS (2, 4, 6 cycles) have been used to improve photoanodes sensitivity through the successive ionic layer adsorption and reaction (SILAR) with a coat of TiO₂ nanoparticles on the ITO substrates. CuS was used as a counter electrode for all cells. The film's behavior was examined in the darkness and under simulated sunlight (200 mW cm⁻²) with electrochemical techniques including chronoamperometry, chronopotentiometry, electrochemical impedance spectroscopy and linear sweep voltammetry. The morphology of the prepared films was investigated by scanning electron microscopy and energy dispersive X-Ray spectroscopy. The results for the TiO₂/2CdS/4PbS film revealed that developing multi-layered cells could improve the quantum dot sensitivity and the performance of the cell in case of reaching the optical layer. The TiO₂/2CdS/4PbS electrode improved the sensitivity of the cell remarkably and the maximum difference between light and darkness was observed in the potential of 1.5 V, in which the constant potential current of 1.5 V led to the cm² difference in chronoamperometry by 18 µA cm⁻².

Keywords: SILAR, Semiconductors, Photoelectrochemical, CdS, PbS

INTRODUCTION

In recent years, photocatalyst has attracted much attention, due to the ability to convert solar energy to electrical energy as well as other diverse applications [1]. Since semiconductors such as ZnO, TiO₂ require ultraviolet light for photocatalytic performance due to their wide bandgaps, finding and designing photocatalysts that can work under visible light is a hot topic. Although CdS is a promising photocatalyst due to the high absorption of visible light and its proper bandgap, two factors, the high recombination of electron and hole couples generated by photo and intensely photo corrosion in pristine CdS, limit the use of this promising substance. To resolve this problem, researchers have introduced composites and heterojunction photocatalysts like graphene/CdS [2-4], CdS/CdSe/ZnS [5] CdS/CdTeS [6], Au,Ag/CdS [7,8], TiO₂/CdS [9,10] MoS₂/CdS [11,12] and other composites based on CdS [13-15]. CdS-based composites have a high photocatalytic activity, especially in the presence of noble metals that, due to high costs, have no industrial application. Therefore, the development of affordable photocatalysts has been of much interest [16]. Lead sulfide (PbS) is an important semiconductor with a narrow bandgap (0.37-0.41 eV) [17-21]. In PbS, an excited electron jumps from the valence band to the conductive band during the light exposure, forming a hole in the valence band. So the electron-hole movement in the lattice structure brings the conductivity properties for PbS. This feature of PbS has drawn much interest from researchers. As studies show, PbS can couple with CdS and the epitaxial growth of PbS on single CdS crystals improves the performance of the cell [22,23]. Changing the stoichiometric parameters of sulfur in the lattice structure of PbS can impart different sorts of PbS
semiconductors including the n-type and the p-type, which are the results of a decrease and an increase in the stoichiometric parameters of sulfur, respectively [24, 25]. Likewise, in recent years, semiconductors of quantum dots (QDs) have attracted attention because of their unique properties [26]. There are various QDs which can be used in solar cells [27-39].

Lots of methods have been employed in developing the thin-film and quantum dot cells such as chemical bath deposition (CBD), electrodeposition (ED), successive ionic layer adsorption and reaction (SILAR) [17]. Use of successive ionic layer adsorption and reaction (SILAR) process for absorption semiconductors such as CdS, PbS, CdSe, etc. is an affordable and facile method for coating the wide-gap semiconductors like TiO$_2$ with a low thickness [18]. Increasing SILAR cycles can also lead to layers with different thicknesses and large particles [19]. This method can improve the performance of the cell at the optical layer [20], since the electron from the radiation of Ti$^{3+}$ (in TiO$_2$ substrate) would be trapped as a result of increasing the number of SILAR cycles, slowing down the kinetics. In this work, 4 layers of CdS and different layers of PbS have been grown on TiO$_2$ film substrate on ITO glass using the SILAR method to create the photoanode electrode.

**EXPERIMENTAL**

**Materials and Methods**

All the chemical materials used in this work were in analytical grade (Merck) and all electrochemical measurements were carried out by the Potentiostat/Galvanostat device (Eg&G, model 273A) controlled by a PC through M270 and M398 software (GPIB interface). Electrochemical Impedance Spectroscopy device (Solartron, model SI 1255) was used to measure the electrochemical properties of the cells in darkness and under simulated sunlight (200 mW cm$^{-2}$) conditions. The surface morphology of the working electrode was investigated by field emission scanning electron microscopy (FESEM), model SIGMA VP (ZEISS company of Germany), also the energy dispersive X-ray spectroscopy (EDS) and mapping detector was made by Oxford Instrument company of England. X-ray diffractometry (XRD) study was performed by X-ray diffractometer model, X’ Pert Pro (Panalytical company). All experiments were performed at temperature of 25°C.

**Preparation of TiO$_2$**

TiO$_2$ paste was prepared by mixing 3 g of titanium dioxide powder with a few drops of diluted acetic acid. To make pores in the TiO$_2$ paste, 0.5 g of carboxymethyl cellulose (CMC) was mixed with 2 ml of ethanol in another beaker. After mixing for 15 min, these two solutions were mixed and stirred with a magnetic stirrer for 1 hr at 50°C to remove ethanol and water. Finally, a few drops of paraffin was added to increase the adhesiveness and viscosity of the TiO$_2$ paste. After cooling off, the TiO$_2$ paste was coated with indium tin oxide glass (ITO) sheet with the resistance of (20-30 Ω/sq) using the doctor blading method and then annealed at 350°C for 1 h. To minimize cracking, the glass should be heated at a slow pace. To make the photoanode, TiO$_2$ film glass was coated with CdS and PbS, respectively, using successive ionic layer adsorption and reaction (SILAR) method. The size of sensitized electrodes (photoanode and photocathode) was 1 cm$^2$.

**Preparation of Photoanodes**

Cd(NO$_3$)$_2$ (0.1 M) and Na$_2$S (0.1 M) were used as precursors to fabricate the CdS layer. The TiO$_2$ film was dip-coated into the Cd(NO$_3$)$_2$ solution for 1 s and subsequently into Na$_2$S for 1 s. At last, the electrode was rinsed with distilled water to remove unadsorbed particles, then dried with a dryer. This procedure was repeated for four times to fabricate 4 layers of CdS on the TiO$_2$ film. To improve the sensitivity of photoanode, different layers of n-type PbS semiconductor was grown on the CdS film. Pb(NO$_3$)$_2$ (0.1 M) and Na$_2$S (0.1 M) were used as precursors. PbS film was coated on CdS by dipping CdS film alternately into the Pb(NO$_3$)$_2$ and Na$_2$S for 1s (SILAR method) and then rinsed with distilled water, this was repeated to create different numbers of SILAR cycles such as 2, 4 and 6 to obtain the different thicknesses of TiO$_2$/4CdS/nPbS layers.

**Preparation of Photocathodes**

SILAR deposition of CuS onto the ITO glass was performed to prepare CEs. CuSO$_4$ (0.1 M) and Na$_2$S (0.1 M) were used as precursors. ITO glass was then immersed in
the CuSO$_4$ solution for 1 min and then dipped in the Na$_2$S solution for another 1 min. Then, the counter electrode was rinsed with distilled water and dried with a dryer. This operation was repeated for four times to make the 4CuS layers.

**Assembling the Cell**

At last, the two coated glass sides were attached by binder clips where the layer of TiO$_2$/4CdS/nPbS was the photoanode and CuS was the photocathode (Fig. 1). It should be noted that no electrolyte was injected into the cell.

**RESULTS AND DISCUSSION**

**Structure of the Prepared Electrode**

Figure 2 shows the SEM images of a mesoporous TiO$_2$ layer onto the ITO glass prepared in the experimental section. According to this figure, the TiO$_2$ layer contains 16-43 nm particles. X-ray diffraction (XRD) technique was used for further study of the structure and the physical properties of the TiO$_2$ film. As shown in Fig. 3, the XRD pattern demonstrated the presence of anatase phase of TiO$_2$. The Scherrer equation was used to calculate the average size of the TiO$_2$ crystal Eq. (1). In this equation, D is the size of the crystals, $\gamma$ is the X-ray wavelength (0.154 nm), $\beta$ is the line broadening at half the maximum intensity (FWHM) and $\theta$ is the Bragg angle.

$$D = \frac{0.9\gamma}{\beta \cos \theta}$$  \hspace{1cm} (1)

The crystal size measured by the Scherrer equation was about 50 nm, which confirmed the nanocrystalline size of the TiO$_2$ film. As already mentioned, the CdS film was sensitized by different layers of n-type PbS using the SILAR cycles to improve efficiency.

The elemental analysis of the TiO$_2$/4CdS/4PbS film is shown in Fig. 4. This spectrum reveals the presence of C, O, S, Ti, Cd, Sn and Pb elements with atomic percentage of 7.55%, 9.33%, 24.78%, 7.31%, 6.68%, 4.03% and 40.32%, respectively. The percentages prove the presence of PbS over the surface of the TiO$_2$/CdS film. Due to the combination of PbS shown in Fig. 4, decrease of sulfur content in the lattice structure leads to the formation of n-type PbS semiconductor. As a result, n-type PbS can improve the sensitivity of the CdS film.

**Photocurrent-voltage Characteristics**

The photocurrent density graph with applied potential (I-V) in dark and under simulated sunlight (200 mW cm$^{-2}$) for different layers of PbS is shown in Fig. 5. Linear sweep voltammetry (LSV) was carried out at the scan rate of 100 (mV s$^{-1}$) in the potential range of -0.3 V to 1.5 V. As illustrated in Fig. 5a, the cell with the lowest current and sensitivity to light and darkness was the TiO$_2$/4CdS/6PbS film, which seems to be the result of the increasing size of the quantum dot particles. Similarly, the TiO$_2$ layer which was slightly coated with CdS and PbS showed less sensitivity to darkness and light in the TiO$_2$/4CdS/2PbS electrode. In the fourth layer of PbS (TiO$_2$/4CdS/4PbS
Fig. 2. SEM images of (a) TiO$_2$ nanoparticles and (b) TiO$_2$/4CdS/4PbS electrode.
Fig. 3. The XRD spectrum of TiO$_2$ paste onto the ITO substrate.

Fig. 4. EDS of TiO$_2$/4CdS/4PbS film with atomic percentage.
film), due to the suitable cover of TiO$_2$ with CdS and PbS, sensitivity and current density were increased. These results indicated that the number of coated layers on the TiO$_2$ film has a vital role in the efficiency and sensitivity of the cells. According to the LSV graph (linear sweep voltammetry) in Fig. 5b, the maximum difference between light and
darkness was observed in the potential of 1.5 V which reached about 13 µA, with CA (chronoamperometry) delivering the same results as well.

**Photoresponse and Photostability of the Prepared Cells**

The photoresponse of TiO$_2$/4CdS/nPbS film was measured by chronoamperometry (CA) and chronopotentiometry (CE) techniques. Film’s behavior was measured in darkness and under chopped light (light on 100s, light off 100s). As shown in Fig. 6a, the TiO$_2$/4CdS/4PbS cell was more sensitive than TiO$_2$/4CdS/2PbS, and TiO$_2$/4CdS/6PbS had the highest photocurrent and was so photoresponsive. Therefore, TiO$_2$/4CdS/4PbS was
considered as the optical layer of photoanodes. For further investigation of TiO$_2$/4CdS/4PbS cell, chronoamperometry was applied at constant four potentials of 0.2, 0.5, 1, 1.5 V (Fig. 6b). The current for TiO$_2$/4CdS/4PbS electrode rises to the maximum immediately after turning the light on and it almost remained unchanged. The light was turned off...
Fig. 9. (a) Nyquist plots for A-TiO$_2$/4CdS/4PbS cell under dark condition, B-TiO$_2$/4CdS/4PbS cell under light illumination, C-industrial cell under dark condition, and D-industrial cell under light illumination. (b)V-t response under light and darkness of A-TiO$_2$/4CdS/4PbS cell, and B-industrial cell for 1000s.
after 100s and the photocurrent of the TiO$_2$/4CdS/4PbS film decreased instantly to the nearly dark current. This was repeated for 1000s and the result showed that the TiO$_2$/4CdS/4PbS cell has the proper stability and fast photoresponse.

The photovoltage of the TiO$_2$/4CdS/4PbS film was measured by the chronopotentiometry technique, under simulated sunlight irradiation (200 mW cm$^{-2}$) (100s dark and 100s light), in 10 µA for 1000s. As shown in Fig. 7, the TiO$_2$/4CdS/4PbS film can reach the potential of 1400 mV potential under visible light illumination. As the generation of an electron in photoanode (TiO$_2$/4CdS/4PbS) and the recombination of the hole in photocathode (CuS) are done to the same extent, the cell reaches a dynamic equilibrium. So, it is expected that the electrode is shifted to the same extent (positively and negatively) whether the light is on or off.

**EIS Characteristics**

The Nyquist spectra of the TiO$_2$/4CdS/4PbS cell under dark and light conditions are shown in Fig. 8, frequency was scanned from 100 KHz to 100 mHz (DC potential of 1 V and AC potential of 15 mV). As illustrated, the beginning and charge-transfer resistance ($R_{ct}$) decreased from 47.58 kOhm, and 531.3 kOhm to 46.79 kOhm, and 496.2 kOhm under light illumination. The beginning resistance in the charts reveals that the cell has become more conductive under illumination, and the charge transfer resistance shows that the electron mobility is improved and the kinetics are fast.

**Comparison the Prepared Cell with an Industrial Cell**

For further review, the TiO$_2$/4CdS/4PbS cell was compared with a silicon industrial cell using chronopotentiometry and applying the current of 10 µA and also using the EIS method with previous conditions. As shown in Fig. 9a, under illumination, the charge transfer resistance was about 1.379 kOhm and the beginning resistance was 16.64 Ohm. In the darkness, the charge transfer resistance and the beginning resistance were 26.78 and 16.91 Ohm, respectively. These values of resistance are very low compared to the TiO$_2$/4CdS/4PbS cell. According to Ohm's law, increasing the resistance would increase the potential Fig. 9b. Thus, the low current density produced by the TiO$_2$/4CdS/4PbS electrode is the result of the high resistances, however, the photoresponse of both cells to darkness and light was the same as Fig. 9b.

**CONCLUSIONS**

In this study, TiO$_2$/4CdS/nPbS quantum dot photoanodes were developed by SILAR method to improve the performance of anode in photocell. According to the experimental studies, TiO$_2$/4CdS/4PbS had the best performance. The TiO$_2$/4CdS/4PbS electrode improved the sensitivity of the cell remarkably and the maximum difference between light and darkness was observed in the potential of 1.5 V, in which the constant potential current of 1.5 V led to the difference in chronomperometry by 18 µA cm$^{-2}$. In fact, the sensitivity and photoresponse of the TiO$_2$ film were improved by using sensitized multi-layered quantum dots while reaching the optical layer of PbS. It should be noted that these results were confirmed by the electrochemical impedance spectroscopy technique.

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**Conflict of Interest**

The authors declare that they have no conflict of interest.

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